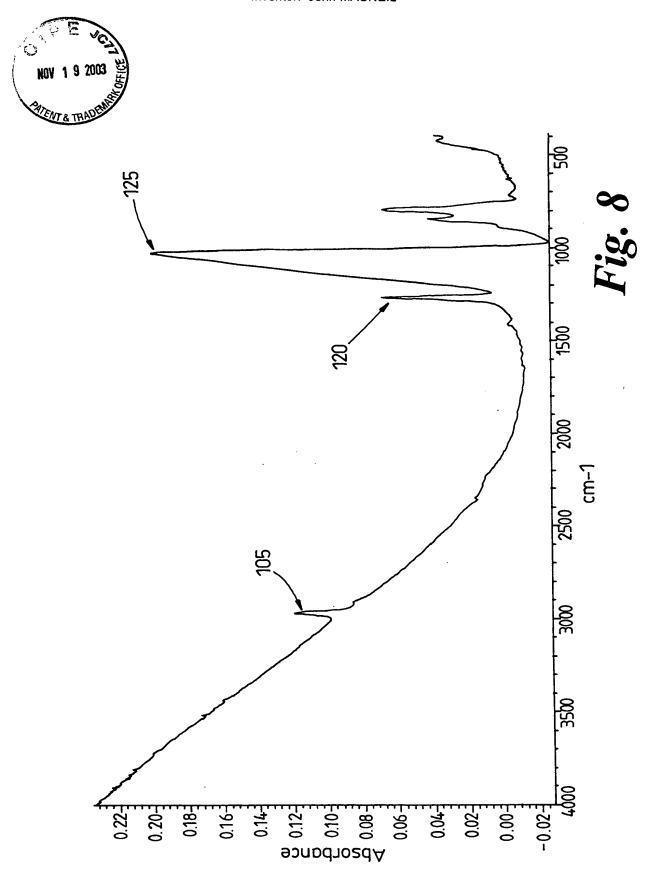
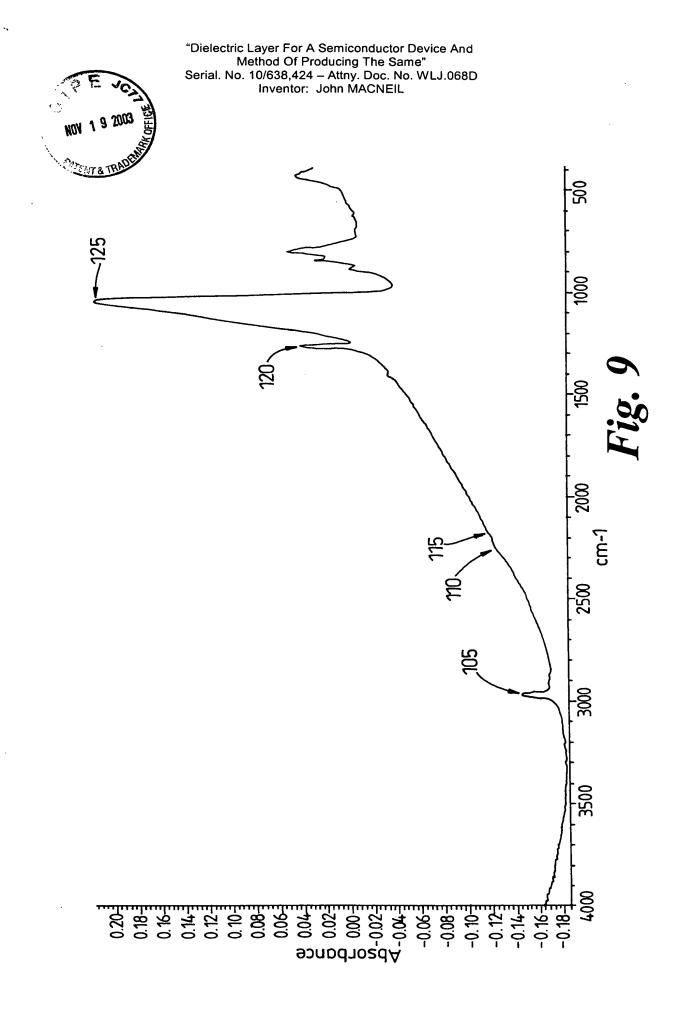
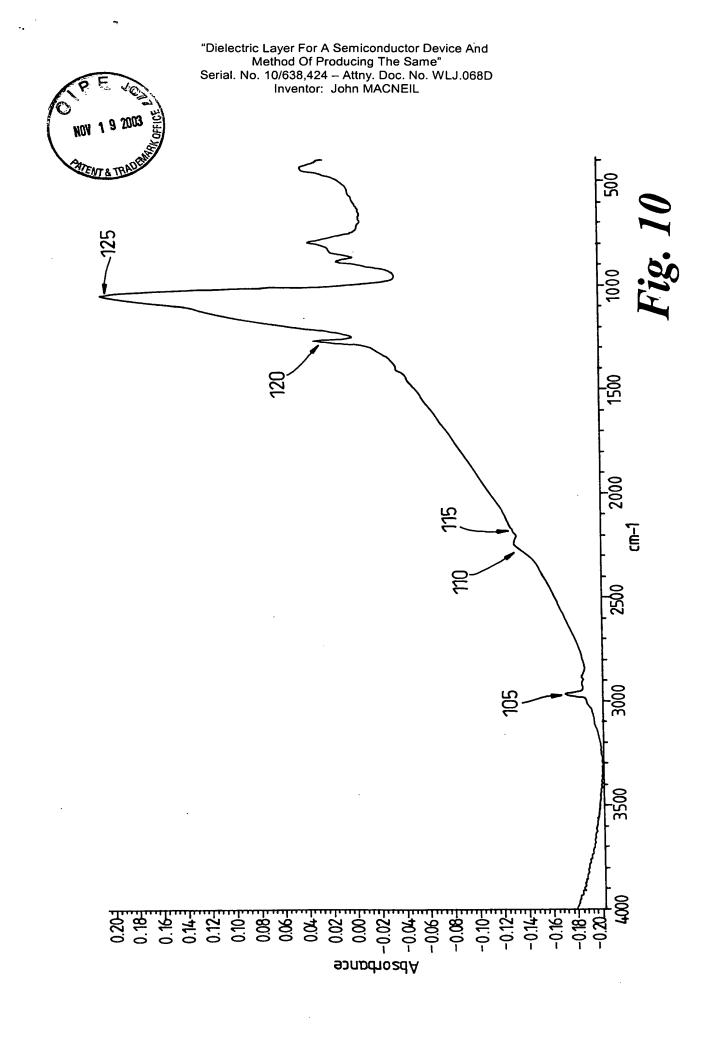


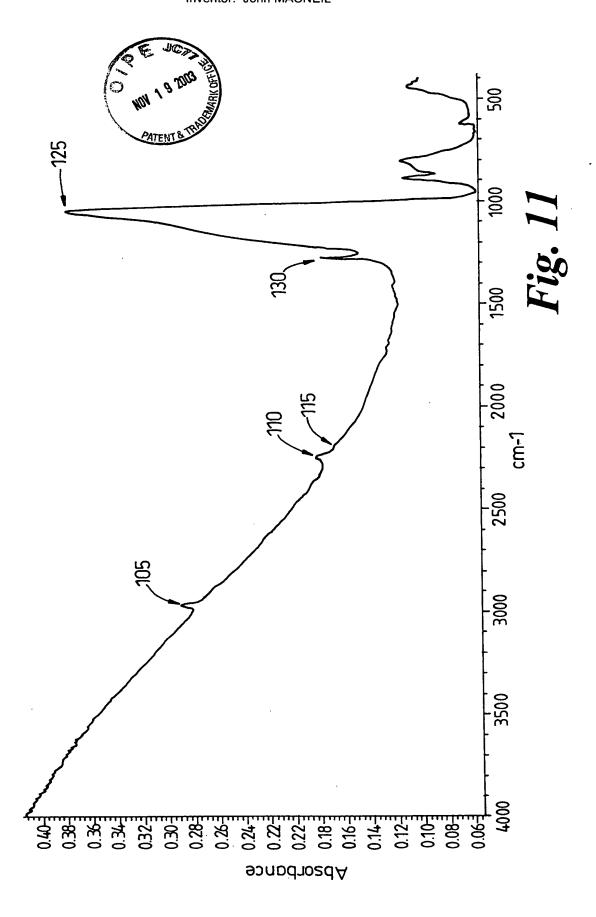
"Dielectric Layer For A Semiconductor Device And Method Of Producing The Same" Serial. No. 10/638,424 – Attny. Doc. No. WLJ.068D Inventor: John MACNEIL



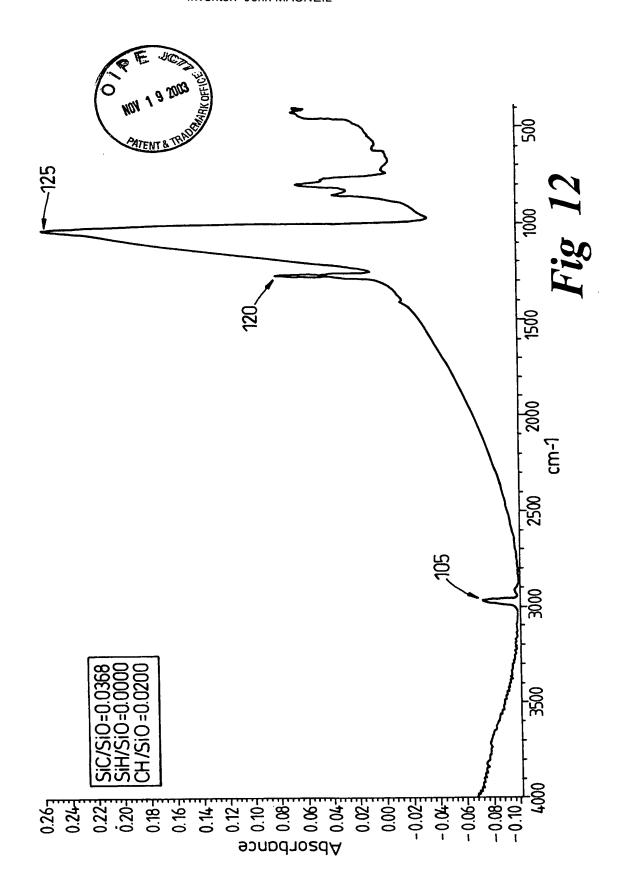




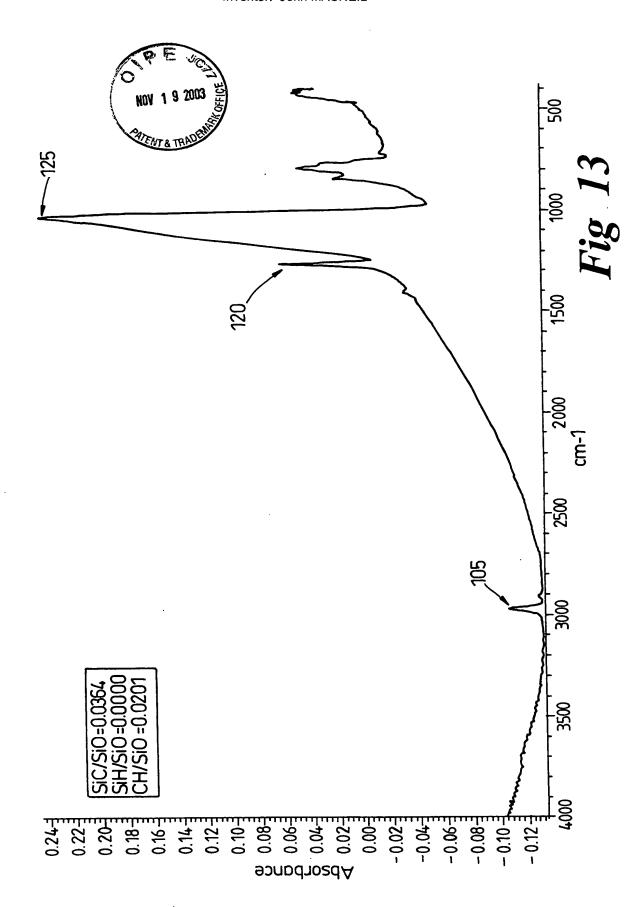
"Dielectric Layer For A Semiconductor Device And Method Of Producing The Same" Serial. No. 10/638,424 – Attny. Doc. No. WLJ.068D Inventor: John MACNEIL



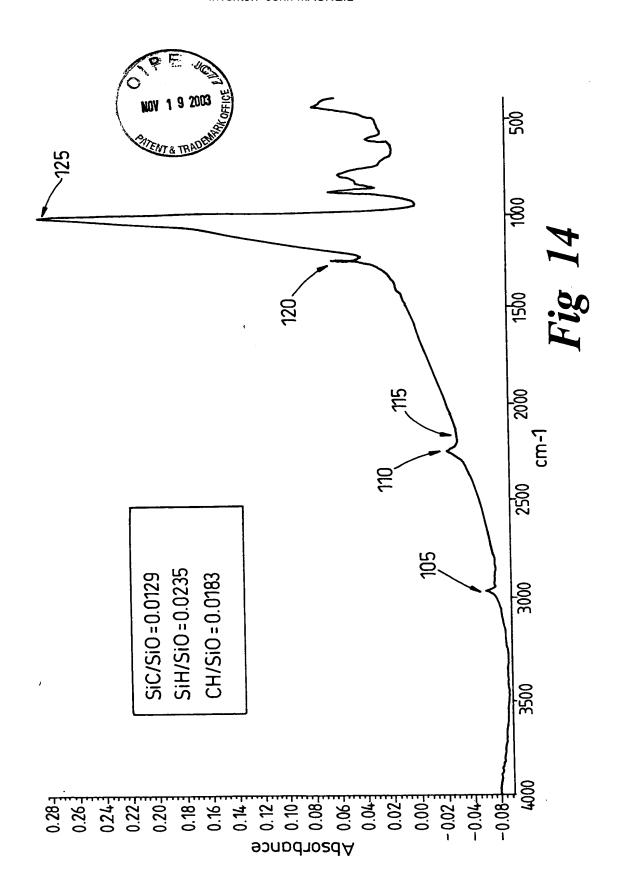
"Dielectric Layer For A Semiconductor Device And Method Of Producing The Same" Serial. No. 10/638,424 – Attny. Doc. No. WLJ.068D Inventor: John MACNEIL



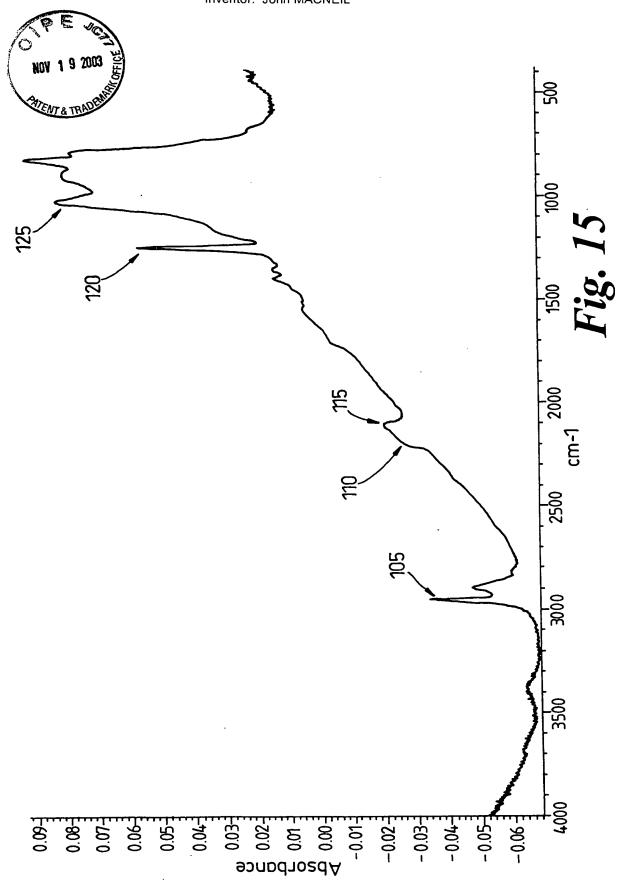
"Dielectric Layer For A Semiconductor Device And Method Of Producing The Same" Serial. No. 10/638,424 – Attny. Doc. No. WLJ.068D Inventor: John MACNEIL



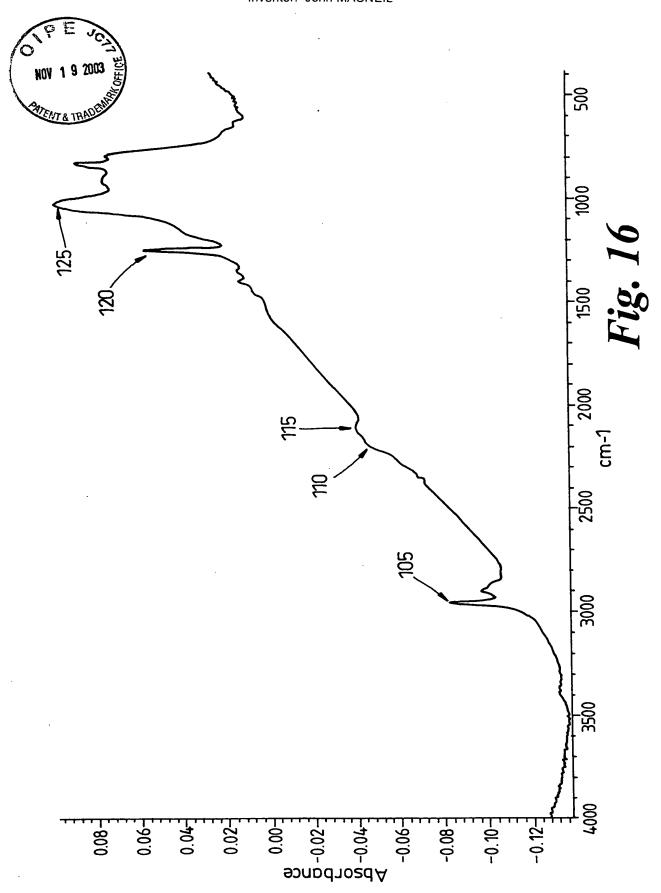
"Dielectric Layer For A Semiconductor Device And Method Of Producing The Same" Serial. No. 10/638,424 – Attny. Doc. No. WLJ.068D Inventor: John MACNEIL



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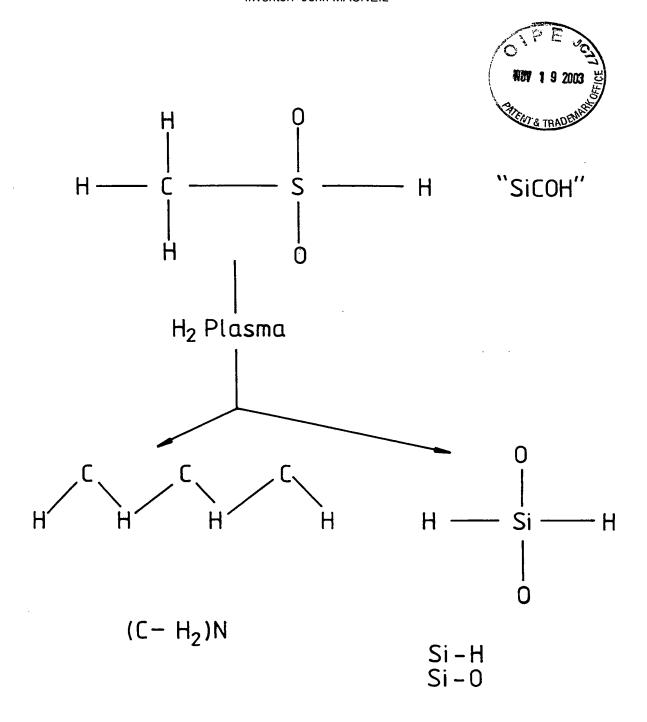


Fig. 17